

Claim 1: Cancelled.

Claim 2: Cancelled.

Claim 3: Cancelled.

Claim 4: Cancelled.

Claim 5: Cancelled.

Claim 6: Cancelled.

Claim 7: Cancelled.

Claim 8: (Original) An illumination equipment for microlithography comprising:
an illumination system, and
a reticle with magnesium fluoride as support material,
in which said illumination system provides radially polarized light and said magnesium
fluoride is oriented with its crystal principal axis substantially in the direction of the
optical axis at said reticle.

Claim 9: (Original) An illumination equipment for microlithography comprising:
an illumination system,
a reticle with support material of transparent optically uniaxial crystal,
in which said illumination system provides radially polarized light and said support
material is oriented with its principal axis substantially in the direction of the optical axis
at said reticle.

Claim 10: (Original) The illumination equipment according to claim 8 or 9 with a
cooling device with a flowing fluid.

Claim 11: Cancelled.

Claim 12: Cancelled.

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Claim 13: Cancelled.

Claim 14: Cancelled.

Claim 15 (Currently amended): A pellicle ~~for use~~ in a microlithographic reticle arrangement consisting of fluoride crystal.

Claim 16: (Original) The pellicle according to claim 15, comprising a fluoride selected from the group consisting of CaF_2 , BaF_2 , or MgF_2 .

Claim 17: Cancelled.

Claim 18: Cancelled.

Claim 19: (Currently amended) An illumination equipment for microlithography comprising:

an illumination system,

a reticle with ~~an optical axis~~ and support material of transparent optically uniaxial crystal, wherein said illumination system provides radially polarized light and said support material is oriented with its principal axis substantially in the direction of said optical axis at said reticle,

further comprising at least one flat plate arranged parallel at said reticle, in which a fluid flows between said reticle and said at least one flat plate.